

Appl. No. 10/072,316
Amdt. Dated May 11, 2004
Reply to Office Action of February 12, 2004

Attorney Docket No. 81751.0029
Customer No.: 26021

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A semiconductor device provided with a memory cell including a first driver transistor, a second driver transistor, a first transfer transistor, a second transfer transistor, a first load transistor and a second load transistor, the semiconductor device comprising:
 - a first gate-gate electrode layer including a gate electrode of the first load transistor and a gate electrode of the first driver transistor;
 - a second gate-gate electrode layer including a gate electrode of the second load transistor and a gate electrode of the second driver transistor;
 - a first drain-drain wiring layer which forms a part of a connection layer that electrically connects a drain region of the first load transistor and a drain region of the first driver transistor;
 - a second drain-drain wiring layer which forms a part of a connection layer that electrically connects a drain region of the second load transistor and a drain region of the second driver transistor;
 - a first drain-gate wiring layer which forms a part of a connection layer that electrically connects the first gate-gate electrode layer and the second drain-drain wiring layer;
 - a second drain-gate wiring layer which forms a part of a connection layer that electrically connects the second gate-gate electrode layer and the first drain-drain wiring layer; and
 - a first active region in which the first load transistor is provided,wherein the first drain-gate wiring layer and the second drain-gate wiring

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layer are located in different ~~layers~~ layer levels, respectively, and
wherein a first protruded active region is provided in a manner to protrude from an end portion of the first active region.

2. (Original) The semiconductor device according to claim 1, wherein the first protruded active region is provided in a manner to protrude on a side opposite to a side where the first and second driver transistors are provided.
3. (Original) The semiconductor device according to claim 1, wherein a part of the first active region and the first protruded active region form an L-shape.
4. (Original) The semiconductor device according to claim 1, comprises:
a second active region in which the second load transistor is provided; and
a second protruded active region provided in a manner to protrude from an end portion of the second active region.
5. (Original) The semiconductor device according to claim 4, wherein the second protruded active region is provided in a manner to protrude on a side opposite to a side where the first and second driver transistors are provided.
6. (Original) The semiconductor device according to claim 4, wherein a part of the second active region and the second protruded active region form an L-shape.

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7. (Original) The semiconductor device according to claim 1,
wherein the first drain-gate wiring layer is electrically connected to the
second drain-drain wiring layer through a contact section, and
wherein the second drain-gate wiring layer is electrically connected to the
second gate-gate electrode layer through a contact section, and electrically
connected to the first drain-drain wiring layer through a contact section.

8. (Original) The semiconductor device according to claim 1, wherein the first
drain-gate wiring layer is located in a layer lower than the second drain-gate wiring
layer.

9. (Original) The semiconductor device according to claim 1, wherein the first
drain-gate wiring layer is located in a layer in which the first gate-gate electrode
layer is provided.

10. (Original) The semiconductor device according to claim 1, wherein the
second drain-gate wiring layer is formed across a plurality of layers.

11. (Original) The semiconductor device according to claim 10,
wherein the second drain-gate wiring layer includes a lower layer of the
second drain-gate wiring layer and an upper layer of the second drain-gate wiring
layer, and
wherein the upper layer is located in a layer over the lower layer, and
electrically connected to the lower layer.

12. (Original) The semiconductor device according to claim 11, wherein the
upper layer is electrically connected to the lower layer through a contact section.

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13. (Currently Amended) The semiconductor device according to claim 11,
wherein the first gate-gate electrode layer, the second gate-gate electrode
layer and the first drain-gate wiring layer are located in a first conductive layer
level,
~~wherein the first drain-drain wiring layer, the second drain-drain wiring~~
layer and the lower layer are located in a second conductive layer level, and
wherein the upper layer is located in a third conductive layer level.
14. (Currently Amended) The semiconductor device according to claim 13,
wherein the second conductive layer level is a nitride layer of a refractory metal.
15. (Currently Amended) The semiconductor device according to claim ~~1~~ 13,
wherein the second conductive layer has a thickness of 100 nm to 200 nm.
16. (Cancelled)
17. (Previously Presented) A memory system provided with the semiconductor
device defined in any one of claims 1 to 15.
18. (Previously Presented) An electronic apparatus provided with the
semiconductor device defined in any one of claims 1 to 15.